

Pulsed Laser Deposition with the Thomas Jefferson National Accelerator Facility Free Electron Laser: Benefits of Sub-Picosecond Pulses with High Repetition Rate

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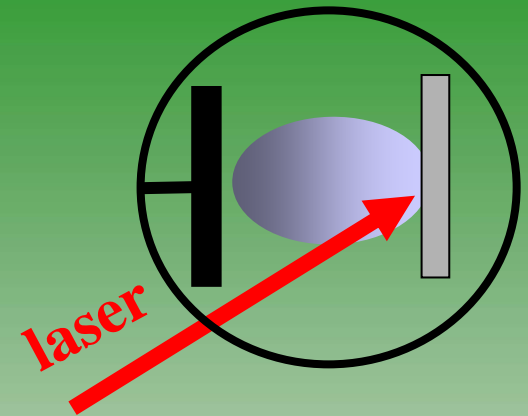
Summary

The TJNAF-FEL presents unique opportunities in PLD with sub-picosecond pulses, high average power, high repetition rate and tunability.

- Plumes dominated by blackbody radiation
- Produces good films with high deposition rates



Why pulsed laser ablation and deposition with the FEL?



Advantages of PLD:

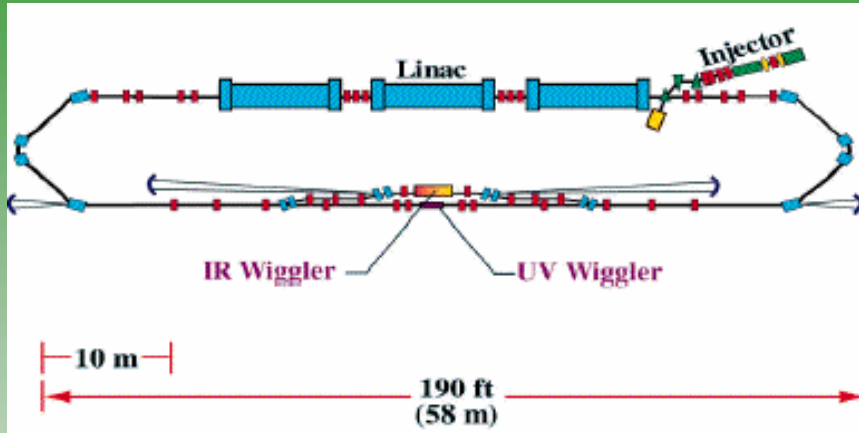
- FLEXIBLE
- GREATER CONTROL OVER ENVIRONMENT
- COMPLEX ALLOYING (High T_c superconductors)
- EPITAXY AT LOW TEMPERATURE

Currently, PLD is limited due to lack of understanding of fundamental processes of laser-target and laser-plasma interactions. Laser sources have been limited.



TJNAF- FEL

Unique *combination of parameters*



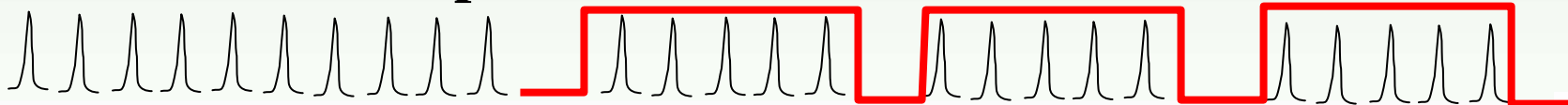
ULTRAFAST (650 fs)

HIGH POWER (>2 kW, 100 μ J/pulse)

TUNABLE (1-6 μ m, THz and UV upgrade)

HIGH REPETITION RATE (18, 34, 74 MHz)

CW or Pulsed Operation



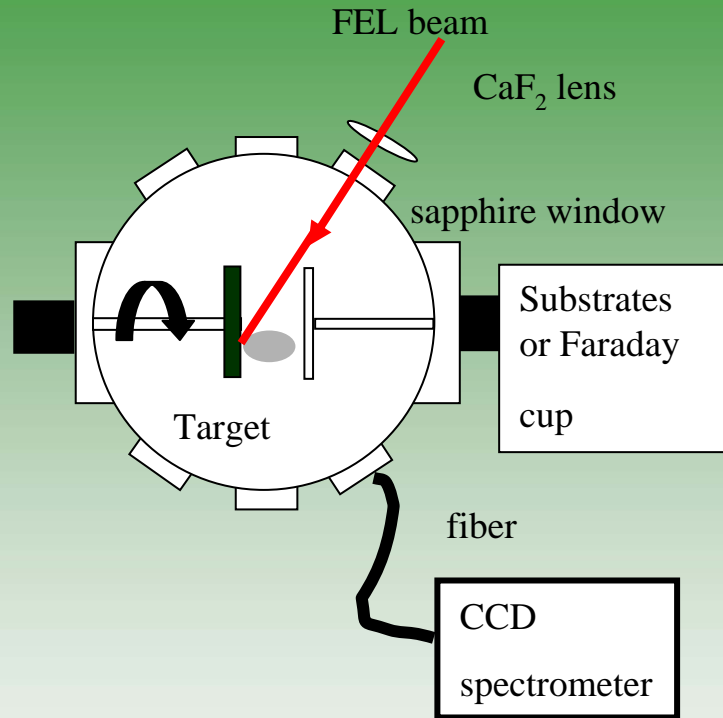
Why PLD with the FEL?

Benefits:

- **ULTRAFAST**: Lower ablation threshold, less target damage, eliminates particulate problem
Gamaly *et al.*, Physics of Plasmas, **9** 949 (2002)
- **HIGH REPETITION RATE**: High deposition rate
Gamaly *et al.*, J. Appl. Phys., **85** 4213 (1999)
- **TUNABLE**: Enhanced ablation/deposition with resonant absorption
Park and Haglund, Appl. Phys. A, **64** 431 (1997)
D. M. Bubb *et al.*, Appl. Phys. Lett, **79** 2847 (2002)



FEL-PLD experimental setup

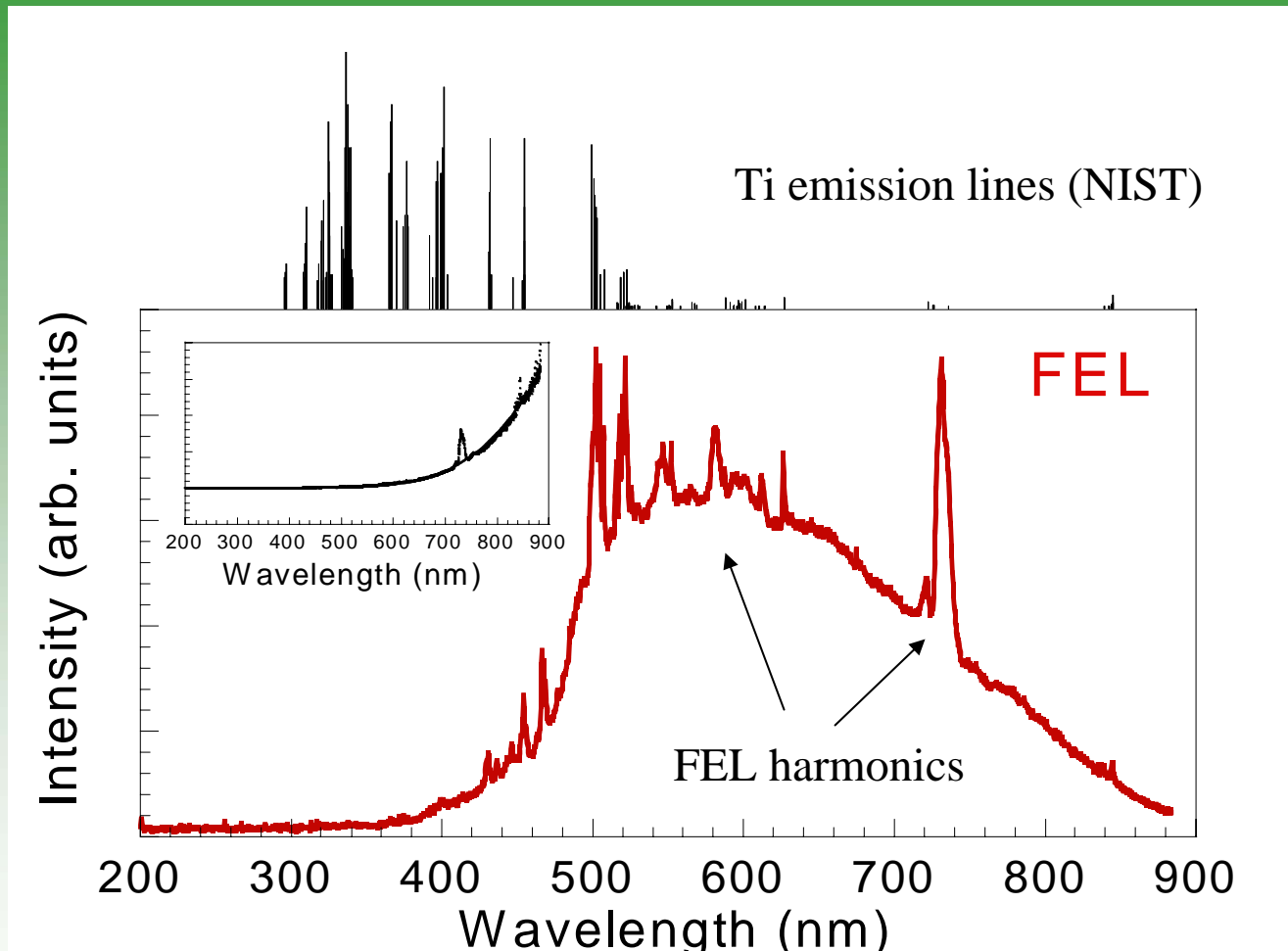


8" Chamber, 1×10^{-6} Torr
FEL at $3.1 \mu\text{m}$



FEL plasma plume
Nb target, cw beam, $\sim 0.6 \text{ J/cm}^2$

Optical spectra shows significant blackbody emission:

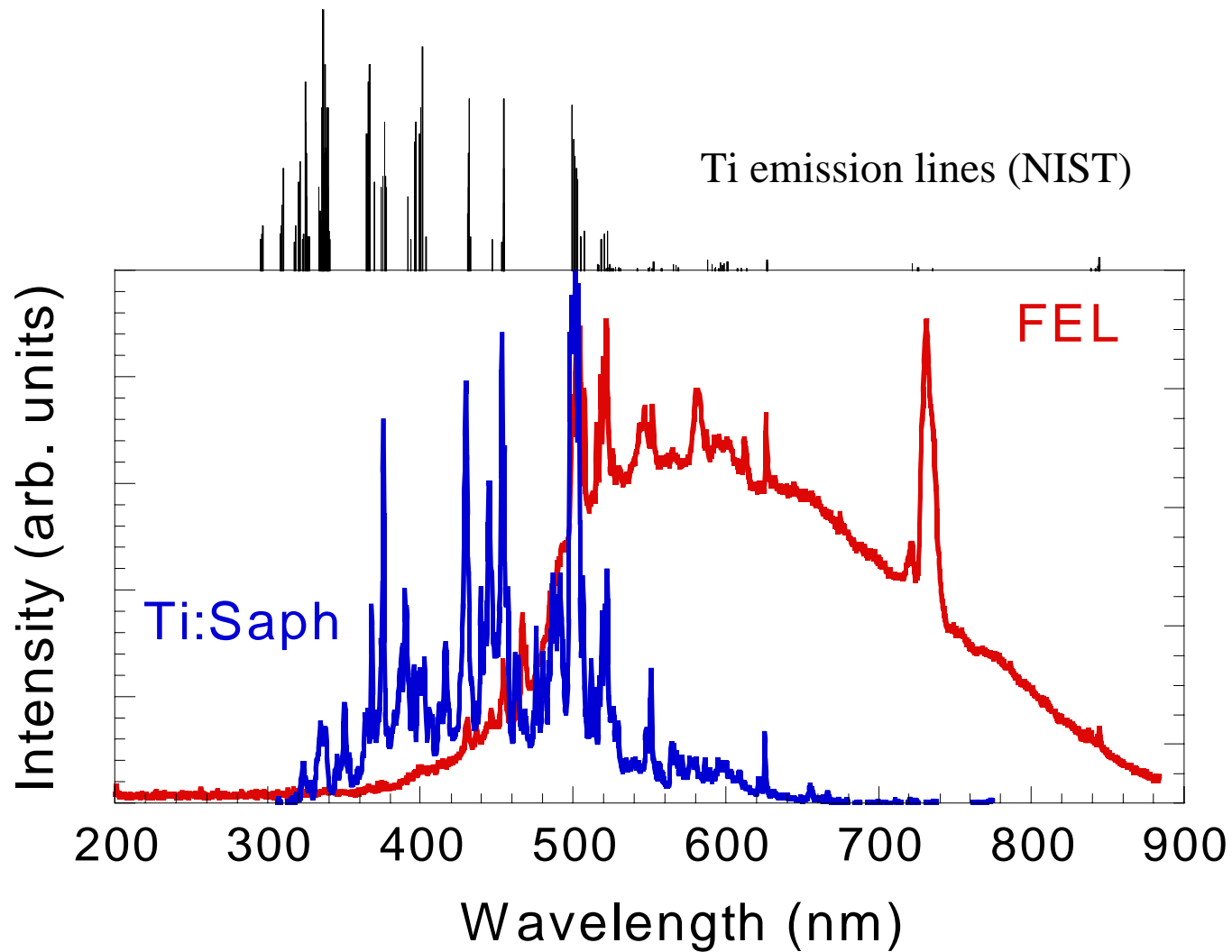


Titanium target

Red curve uncorrected response



Compared with amplified Ti:Saph ablation (1 mJ/pulse, 1 kHz):



Blackbody radiation with FEL ablation:

Dense Plasma?

G. Mehlman *et al.*, J. Appl. Phys., **74** 53 (1993)

Heating of nanoparticles?

D. B. Geohegan *et al.*, Appl. Phys. Lett., **62** 1463 (1993)



Thin Film Quality (Magnetic Materials)

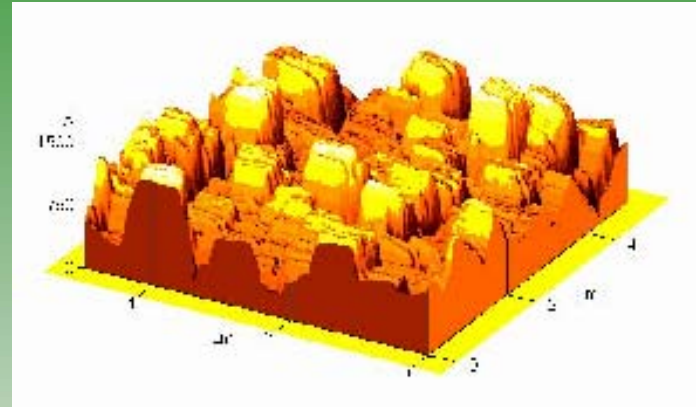
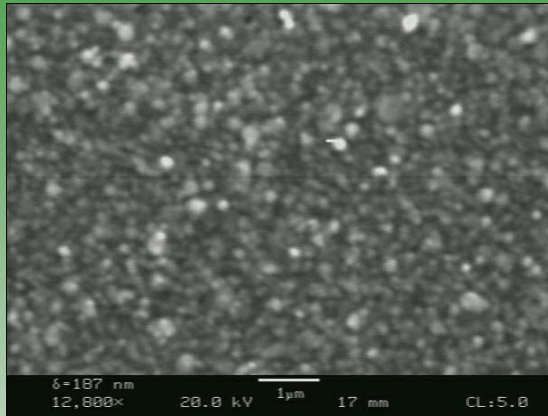
**Benefit of sub-picosecond pulses and high repetition rate:
high quality films with high deposition rates**

**Demonstrated in comparison to amplified Ti:Sapphire
system (150 fs, 1 mJ/pulse, 1 kHz)**

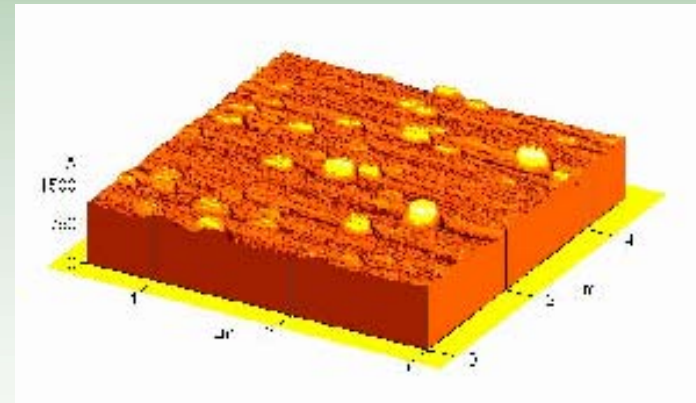
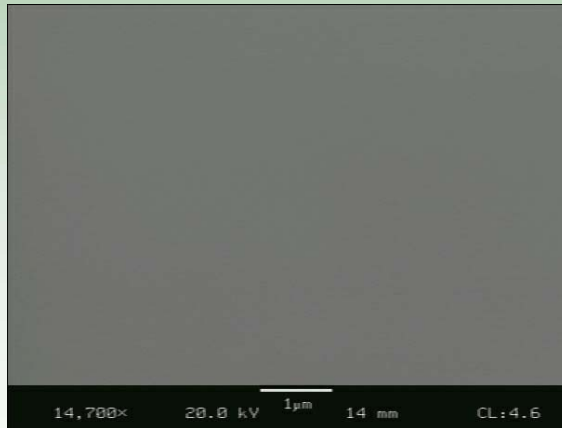
Amplified Ti:Sapphire versus FEL (NiFe)

Exploring dependence on pulse power and repetition rate

Amplified TS
0.7 mJ/1 kHz



FEL
5 μJ/37.4 MHz



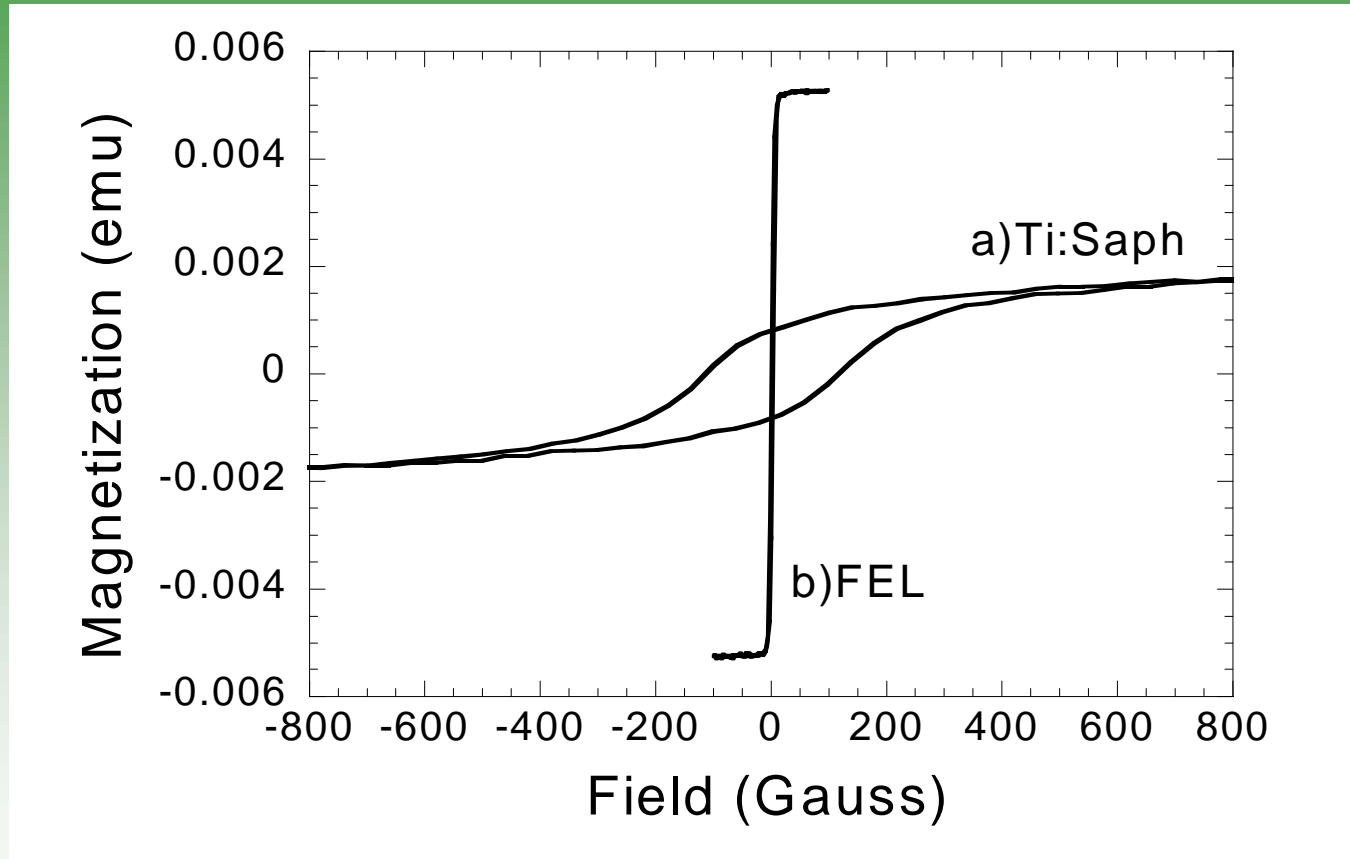
SEM

AFM



Amplified Ti:Sapphire versus FEL (NiFe)

Large effect on magnetic properties



Crystallized Fe? Crystalline orientation? Roughness?



Amplified Ti:Sapphire versus FEL (NiFe)

Deposition Rates

Amp. Ti:Saph

1 mJ/pulse, 1 kHz

1 Å/s

1×10^{-3} Å /pulse

FEL

5 μJ/pulse, 37.4 MHz

17 Å/s

5×10^{-7} Å /pulse

Possibility of much higher rates with FEL:

200 Å/s for Nb M. Shinn, Proc. SPIE (2000)



Conclusions

- The TJNAF-FEL gives a unique combination of laser parameters
- Interesting opportunities to explore laser-target and laser-plasma interactions
- FEL-PLD gives high quality films with very high deposition rates

